

UNITED STATES DEPARTMENT OF COMMERCE
Patent and Trademark Office
Address: COMMISSIONER OF PATENTS AND TRADEMARKS
Washington, D.C. 20231

SERIAL NUMBER	REQUEST DATE	FIRST NAMED APPLICANT	ATTORNEY DOCKET NO.
10/552,606	3/24/06	TOMOHARU NAKANO, ET AL.	052463

Title: **POLISHING LIQUID FOR CMP PROCESS AND
POLISHING METHOD**

--

Art Unit	Paper Number
----------	--------------

Correspondence Address:

SHUJI YOSHIZAKI
WESTERMAN, HATTORI, DANIELS & ADRIAN LLP.
1250 CONNECTICUT AVE., STE 700
WASHINGTON, D.C. 20036

Licensee under 35 U.S.C. 184 is hereby granted to file in any foreign country a patent application and any amendments thereto corresponding to the subject matter of this U.S. application identified above and/or any material accompanying the petition. This license is conditioned upon modification of any applicable secrecy order and is subject to revocation without notice.

License Number: 536,830

Grant Date: 10-Aug-06

**This license is granted retroactively to
the date(s) and the country(s) indicated
on the attached decision.**

Approved:


for Commissioner of Patents and Trademarks

This license empowers the filing, the causation and the authorization of the filing of a foreign application or applications on the subject matter identified above, subsequent forwarding of all duplicate and formal papers and the prosecution of such application or applications.

This license does not empower the filing of any applications, amendments, supplements or continuances originating in this country which disclose inventions, modifications, or variations not disclosed in the subject matter identified above.

This license is to be retained by the licensee and may be used at anytime on or after the date thereof. This license is not retroactive unless specifically indicated.

The grant of this license does not in any way lessen the responsibility of the licensee for the security of the subject matter as imposed by any Government contract or the provisions of existing laws relating to espionage and the national security or the export of technical data. Licensees should apprise themselves of current regulations, especially with respect to certain countries, of other agencies, particularly the Office of Foreign Assets Control, Department of the Treasury; Office of Munitions Control, Department of State (with respect to Arms, Munitions and Implements of War); the Bureau of Trade Regulation, Office of Export Administration, Department of Commerce; and the Department of Energy.

LICENSE FOR FOREIGN FILING

[Title 35, United States Code (1952) Sections 184, 185, 186]



UNITED STATES PATENT AND TRADEMARK OFFICE

COMMISSIONER FOR PATENTS
UNITED STATES PATENT AND TRADEMARK OFFICE
WASHINGTON, D.C. 20231
www.uspto.gov

Petitioner: NAKANO, et al. :DECISION ON REQUEST
Petition No.: 10/552,606 :UNDER 37 CFR 5.25
Petition Filing Date: 24 March 2006
Docket No.: 052463

Title: POLISHING LIQUID FOR CMP PROCESS AND POLISHING METHOD

This is a decision on the petition for retroactive foreign filing license.

It has been determined that a retroactive license for foreign filing under 35 U.S.C. 184 be granted with respect to the filing(s) listed below. The petition complies with 37 C.F.R. 5.25 in that there is an adequate showing that the subject matter in question was not under secrecy order, that the license was diligently sought, and that the material was filed abroad without the required license under 37 C.F.R 5.11 through error and without deceptive intent.

Foreign Filing Location

Date

Japan

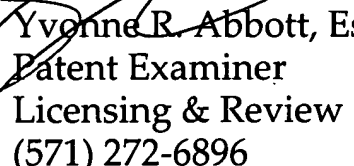
07 May 2004

Taiwan

07 May 2004

Malaysia

07 May 2004


Yvonne R. Abbott, Esq.
Patent Examiner
Licensing & Review
(571) 272-6896